

Appl. No. : 10/692,243
Filed : October 22, 2003

AMENDMENTS TO THE SPECIFICATION

Please replace the paragraph beginning on page 1 after "BACKGROUND OF THE INVENTION" with the following replacement paragraph:

This application is a divisional of U.S. Application No. 09/866,156, filed May 24, 2001, now U.S. Patent No. 6,652,924, which is a divisional of U.S. Application No. 09/291,807, filed April 14, 1999, now U.S. Patent No. 6,342,277, which is in turn a continuation-in-part of U.S. Application No. ~~08/669,002~~ 08/699,002, filed on August 16, 1996, now U.S. Patent No. 5,916,365, each of which is incorporated herein by reference. The present invention relates to methods and apparatuses suited to the low temperature deposition of solid thin films of one or more elements by the technique of sequentially exposing the object being coated with chemically reactive gaseous species. It also describes a number of applications of films produced by such processes.